

Lithography Training Course – A Raith Webinar enabling exposures on Gemini-based Systems

Date and Time: 28 September – 30 September, 2021; 08:30 – 16:30, CET

Venue: MS Teams

Tuesday, 28 September 2021

08:30 – 09:15	Welcome! Who we are Learn about projects, desktop and editor Axel Rudzinski
09:30 – 10:15	Position list set up, current measurement Axel Rudzinski
11:15 – 12:00	Parameter definition, coordinate systems Axel Rudzinski
12:00 – 13:15	LUNCH BREAK
13:15 – 14:00	Exposure preparation on eLINE demo system Axel Rudzinski
14:00 – 16:00	Afternoon exercise: Do your first exposure! Follow the step-by-step guide! Develop and inspect
16:00 – 16:30	Q&A arising from first exposure all

Wednesday, 29 September 2021

08:30 – 09:15	Exposure preparation: What was that again? Axel Rudzinski
09:30 – 10:15	Thumb of rules for exposure parameter and Nav for sample inspection Axel Rudzinski
11:15 – 12:00	Pattern inspection for lazy people (imaging and measurement) Axel Rudzinski
12:00 – 13:15	LUNCH BREAK
13:15 – 14:00	Overlay exposure preparation on eLINE demo system Axel Rudzinski
14:00 – 16:00	Afternoon exercise: Do your first overlay exposure!
16:00 – 16:30	Q&A arising from first overlay exposure all

Thursday, 30 September 2021

08:30 – 09:15	Overlay exposure preparation: What was that again? Axel Rudzinski
09:30 – 10:15	Inspect Overlay results, Trainer is lazy Axel Rudzinski
11:15 – 12:00	Discussion about Customer pattern all
12:00 – 13:15	LUNCH BREAK
13:15 – 14:00	Exposure and inspection of customer pattern Axel Rudzinski
14:00 – 16:00	Afternoon exercise: Exposure your own pattern (partly with dose variation)
16:00 – 16:30	Q&A arising from first customer pattern exposure Axel Rudzinski